



International Workshop on Junction Technology 2025

25th Anniversary Special Workshop & 100th Anniversary FET Invention

June 4th, 2025

Kyoto University, Uji Campus

Part 1 Junction Technology Review

10:00 – 14:50

Keynote:

“Tracing the Roots of Junction Technology: 25 Years of IWJT and the Centennial of FET”

by Prof. H. Iwai, National Yang Ming Chiao Tung University

Technology Overview, Invited:

- Plasma Doping: Dr. B. Mizuno, UJT Lab.
- Epi Doping: Dr. J. Borland, JOB Technologies
- Ion Channeling: Dr. M. Current, Current Scientific
- As Cluster Structure: Prof. K. Tsutsui, Institute of Science Tokyo
- Cluster I/I: Prof. J. Matsuo, Kyoto University
- I/I Equipment: Dr. M. Tanjo, DC Center Come
- Silicide: Prof. O. Nakatsuka, Nagoya University
- Device Technology: Prof. Wakabayashi, Institute of Science Tokyo

Part 2 Panel Discussion

15:10-17:10

“25 Years of IWJT, FET100, and Future Directions in Junction Technology”

- Intensive exchange, not only recalling past technologies
but also addressing current issues and exploring future directions -

- Moderator : Dr. H. Ito, Applied Materials, Inc.
& Dr. I. Mizushima, NuFlare Technology Inc.
- Panelist: Past IWJT program chairs & Dr. M. Current,
Dr. J. Borland, Prof. J. Matsuo and Prof. H. Iwai etc.